

Amendments to the Claims:

This listing of claims replaces all prior versions and listings of claims in the application.

In the Claims:

1. (Currently Amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, ~~said~~ the device comprising:

a body having an opening to receive ~~said~~ the nanolithography template, ~~said~~ the body for positioning ~~said~~ the template relative to ~~said~~ the substrate for imprinting ~~said~~ the nanolithography pattern on ~~said~~ the substrate; and

a supporting plate coupled to ~~said~~ the body and positioned relative to ~~said~~ the nanolithography template to support a force of ~~said~~ the imprinting on ~~said~~ the nanolithography template, with ~~said~~ the supporting plate being substantially transparent to a curing agent; and,

a piezo system coupled to the body to vary dimensions of the nanolithography template.

2. (Currently Amended) The device as recited in claim 1 wherein ~~said~~ the curing agent comprises ultraviolet radiation.

3. (Currently Amended) The device as recited in claim 1 wherein ~~said~~ the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

4. (Currently Amended) The device as recited in claim 1 further including a vacuum system in fluid communication with ~~said~~ the supporting plate to apply a vacuum to ~~said~~ the nanolithography template.

5. (Currently Amended) The device as recited in claim 1 further including a vacuum system in fluid communication with ~~said~~ the supporting plate to apply a vacuum between ~~said~~ the supporting plate and ~~said~~ the body.

6. (Currently Amended) The device as recited in claim 1 wherein ~~said~~ the supporting plate is configured to reduce deformation of ~~said~~ the nanolithography template due to forces present during an imprint lithography process.

7. (Currently Amended) The device as recited in claim 1 further including a reflective element connected to a portion of ~~said~~ the body located within ~~said~~ the opening.

8. (Currently Amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, ~~said~~ the device comprising:

a body having an opening to receive ~~said~~ the nanolithography template, ~~said~~ the body for positioning ~~said~~ the template relative to ~~said~~ the substrate for imprinting ~~said~~ the nanolithography pattern on ~~said~~ the substrate; and

a supporting plate coupled to ~~said~~ the body and positioned relative to ~~said~~ the nanolithography template to support a force of ~~said~~ the imprinting on ~~said~~ the nanolithography template, with ~~said~~ the supporting plate substantially transparent to ultraviolet radiation; and,

a piezo system coupled to said body to vary dimensions of said nanolithography template.

9. (Currently Amended) The device as recited in claim 8 wherein ~~said~~ the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

10. (Currently Amended) The device as recited in claim 8 further including a vacuum system in fluid communication with ~~said~~ the supporting plate to apply a vacuum to ~~said~~ the nanolithography template.

11. (Currently Amended) The device as recited in claim 8 further including a vacuum system in fluid communication with ~~said~~ the supporting plate to apply a vacuum between ~~said~~ the supporting plate and ~~said~~ the body.

12. (Currently Amended) The device as recited in claim 8 wherein ~~said~~ the supporting plate is configured to reduce deformation of ~~said~~ the nanolithography template due to forces present during an imprint lithography process.

13. (Currently Amended) The device as recited in claim 8 further including a reflective element connected to a portion of ~~said~~ the body located within ~~said~~ the opening.

14. (Currently Amended) A device for holding a nanolithography template used for imprinting a nanolithography pattern on a substrate, ~~said~~ the device comprising:

a body having an opening to receive ~~said~~ the nanolithography template, ~~said~~ the body for positioning ~~said~~ the template relative to ~~said~~ the substrate for imprinting ~~said~~ the nanolithography pattern on ~~said~~ the substrate;

a supporting plate coupled to ~~said~~ the body and positioned relative to ~~said~~ the nanolithography template to support a force of ~~said~~ the imprinting on ~~said~~ the nanolithography template, with ~~said~~ the supporting plate substantially transparent to a curing agent

a piezo system coupled to said body to vary dimensions of said nanolithography template; and

a vacuum system in fluid communication with ~~said~~ the supporting plate to apply a vacuum between ~~said~~ the supporting plate and ~~said~~ the body.

15. (Currently Amended) The device as recited in claim 14 wherein ~~said~~ the curing agent comprises ultraviolet radiation.

16. (Currently Amended) The device as recited in claim 14 wherein ~~said~~ the supporting plate is formed from material selected from a set of materials consisting of quartz, sapphire, and silicon dioxide.

17. (Currently Amended) The device as recited in claim 14 wherein ~~said~~ the supporting plate is configured to reduce deformation of ~~said~~ the nanolithography template due to forces present during an imprint lithography process.

18. (Currently Amended) The device as recited in claim 14 further including a reflective element connected to a portion of ~~said~~ the body located within ~~said~~ the opening.